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Plasma Synthesis and Etching of Electronic Materials

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Preface

This volume is a collection of most of the invited and contributed papers presented at the Symposium on Plasma Synthesis and Etching of Electronic Materials held in Boston, Massachusetts on November 27-30, 1984. The symposium covered topics ranging from plasma diagnostics to mechanisms of plasma etching and growth of materials. The spirit of the symposium was to provide a medium for specialists in the field to discuss their latest understanding of the chemistry and physics of plasma-materials interaction. A few overview papers were also given to those in the audience who were new to this fast growing technologically important field. There were six pre-scheduled sessions and one late news session on the last day. All of the sessions were very well attended and there were extensive discussions after most of the talks. We were very please with the favorable response of the attendees!

R.P.H. Chang
B. Abeles
December 1984

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